

Supporting Information

2D WS₂-Edge Functionalized Multi-Channel Carbon Nanofibers: Effect of WS₂ Edge-Abundant Structure on Room-Temperature NO₂ Sensing

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S1. WS₂@CNFs

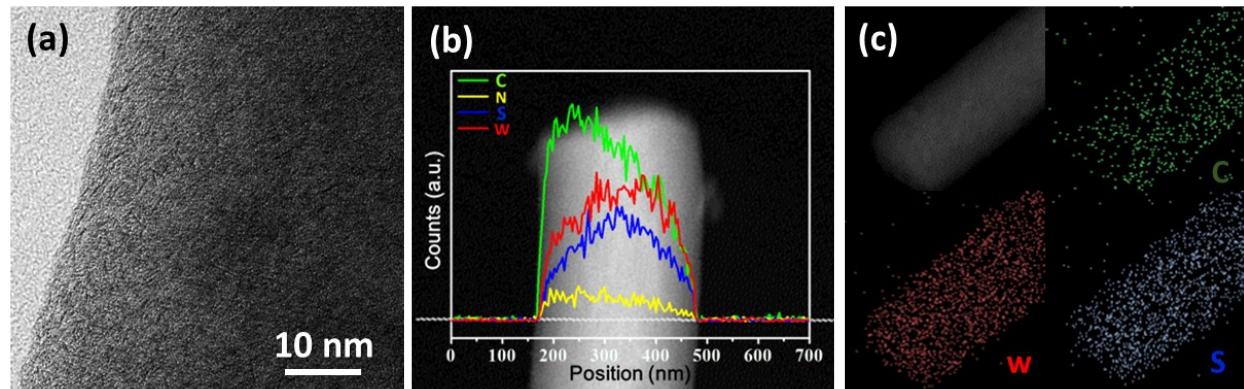


Figure S1. (a) HRTEM image of WS₂@CNFs. (b) STEM image of WS₂@CNFs on which EDS line-scan profile of W,S, N, and C is presented. (c) STEM image and STEM-EDS mapping image of WS₂@CNFs: W (red), S (sky-blue), nad C (green).

S2. TEM images of WS₂@MTCNFs and CNFs

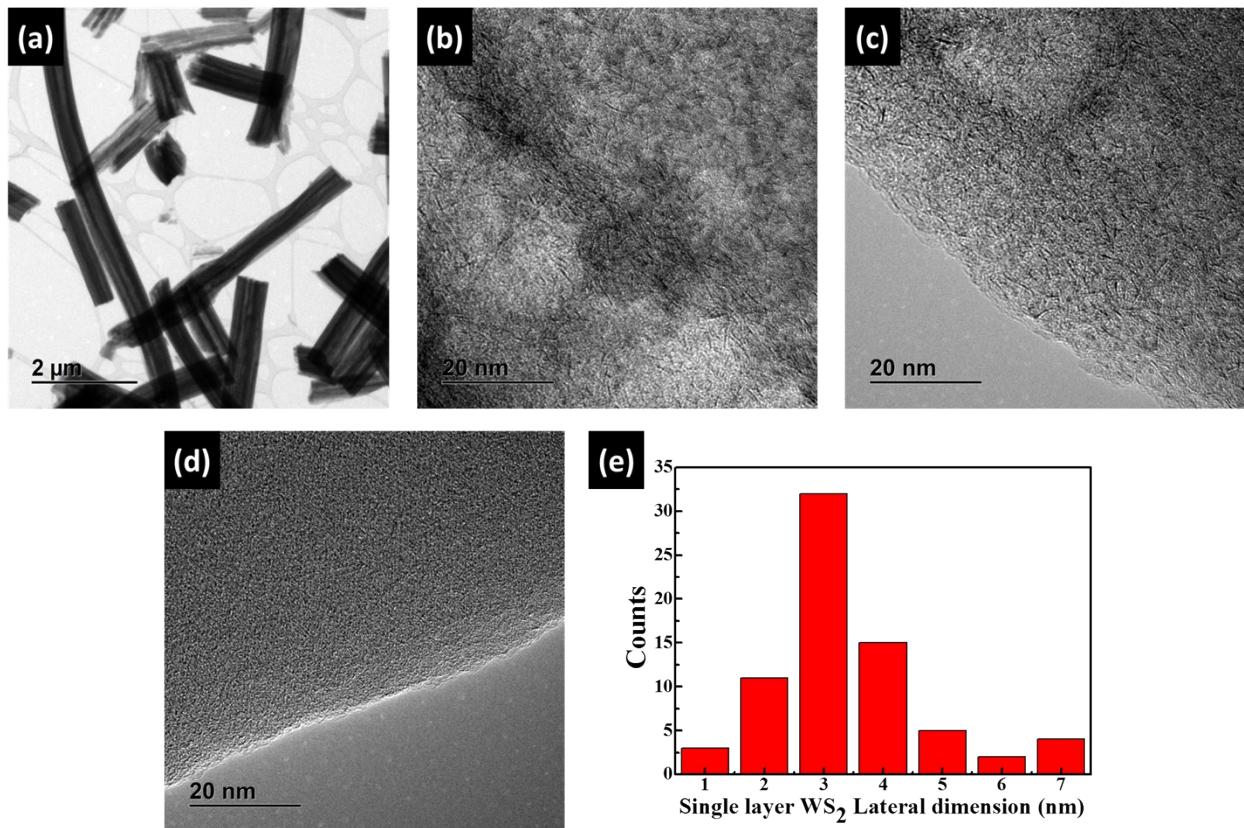


Figure S2. (a) TEM image of WS₂@MTCNFs. HRTEM images of (b-c) WS₂@MTCNFs and (d) CNFs. (e) Lateral dimension size distribution histogram of single layer WS₂ in MTCNFs.

S3. XRD patterns of WS₂@MTCNFs

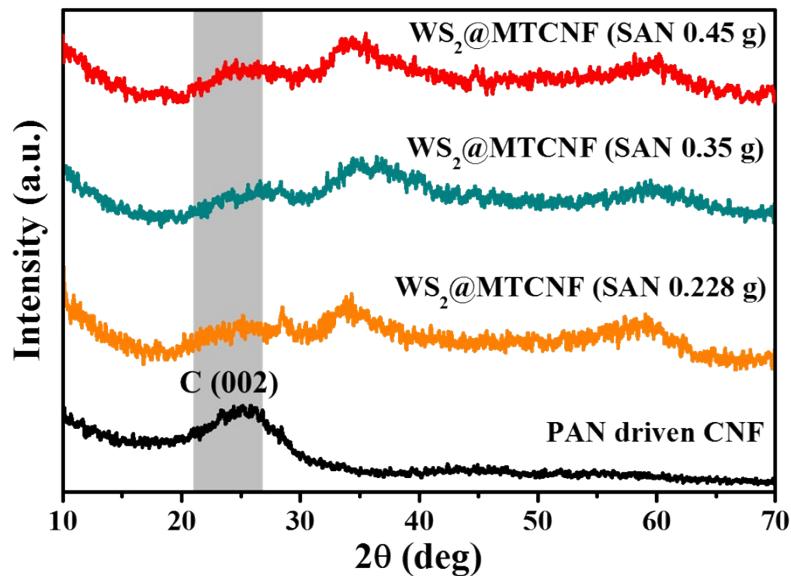


Figure S3. XRD patterns of WS₂@MTCNFs with SAN 0.450 g, SAN 0.350 g, and SAN 0.228 g and PAN-driven CNFs, respectivley.

S4. XPS spectra of the WS₂@MTCNFs : C 1s peaks

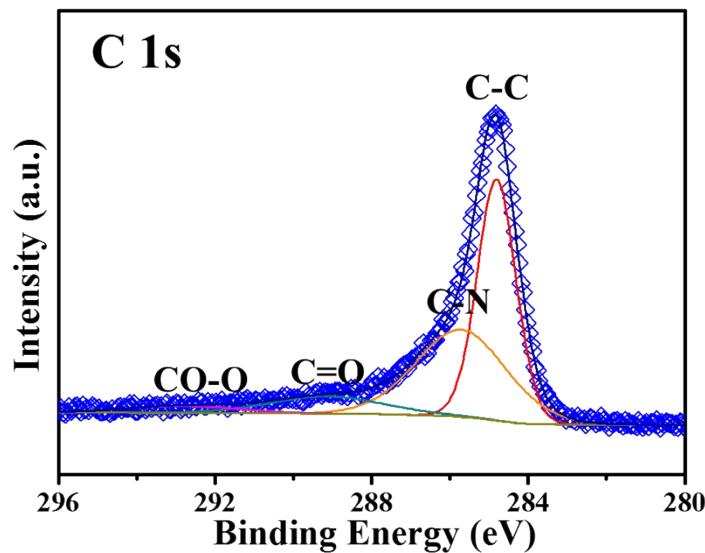


Figure S4. XPS spectra of the WS₂@MTCNFs : C 1s peaks

S5. Ex-situ XPS analysis in humid condition

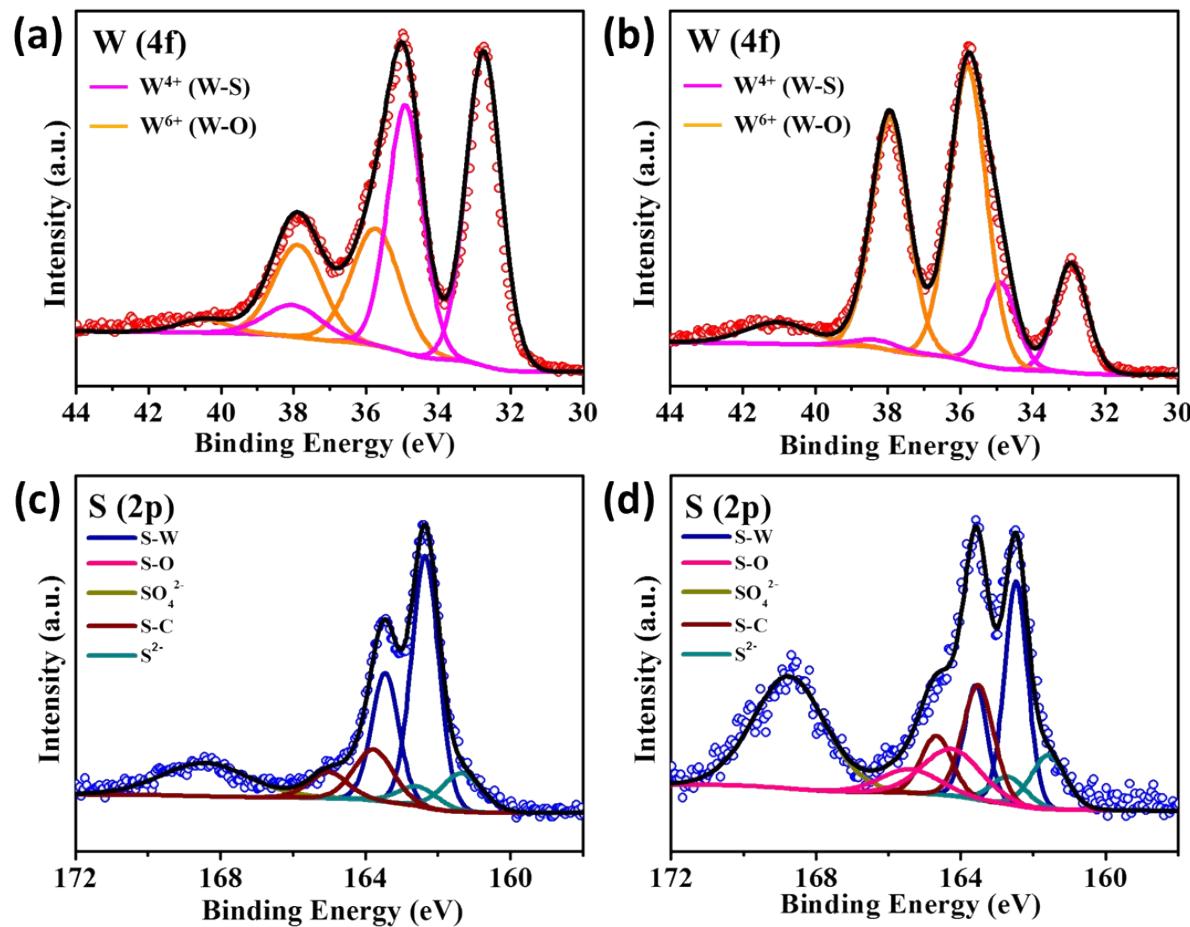


Figure S5. Ex-situ XPS analysis with $\text{WS}_2@\text{MTCNFs}$: W 4f spectra (a) before and (b) after exposure to NO_2 in humid condition. S 2p spectra (c) before and (d) after exposure to NO_2 in humid condition.

S6. Sensing characteristics of CNFs and WS₂@MTCNFs

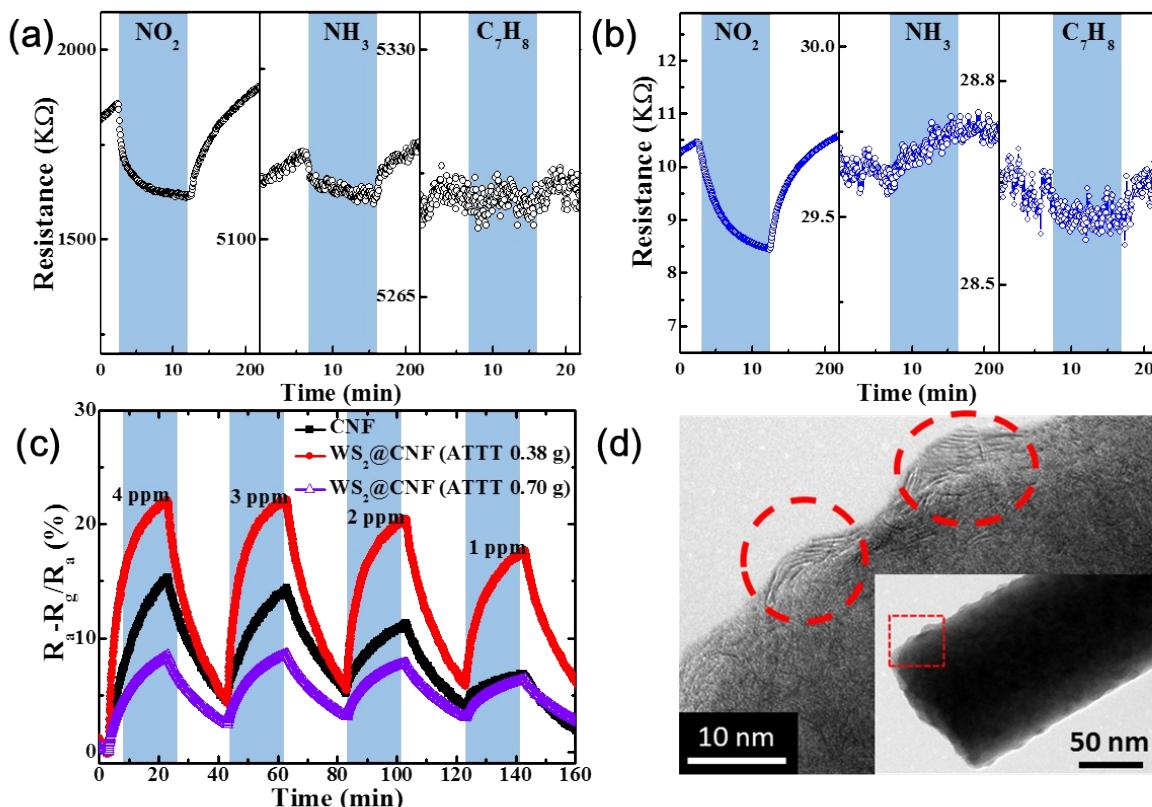


Figure S6. (a) Dynamic resistance transition characteristics of CNFs toward 5 ppm of NO₂, NH₃, and C₇H₈. (b) Dynamic resistance transition characteristics of WS₂@MTCNFs toward 5 ppm of NO₂, NH₃, and C₇H₈. (c) Dynamic response transients of CNFs, WS₂@CNFs (ATTT 0.38 g), and WS₂@CNFs (ATTT 0.7 g) toward NO₂ in the concentration range of 4-1 ppm at room temperature. (d) TEM image and HRTEM image of WS₂@CNFs (ATTT 0.7 g)

The sensing tendency of the dense CNFs and WS₂@MTCNFs toward NH₃ based on resistance might be further supported by edge effects exerted by WS₂ nanoflakes distributed on the surface. During exposure to NH₃, the resistance of the dense CNFs decreases due to the electron

donating property of NH₃ molecules. According to previous studies, carbon-based gas sensors such as carbon nanotubes and graphene exhibiting n-type sensing behavior against reducing gases even though carbon nanofibers exhibit a p-type response in oxidizing gases.¹⁻² In the present study, the resistance of WS₂-edge functionalized CNFs (WS₂@MTCNFs) is increased with no recovery when NH₃ gas was injected, which is identical in sensing tendency toward NH₃ of layered MoS₂.³⁻⁴

S7. Ex-situ XPS analysis in dry condition

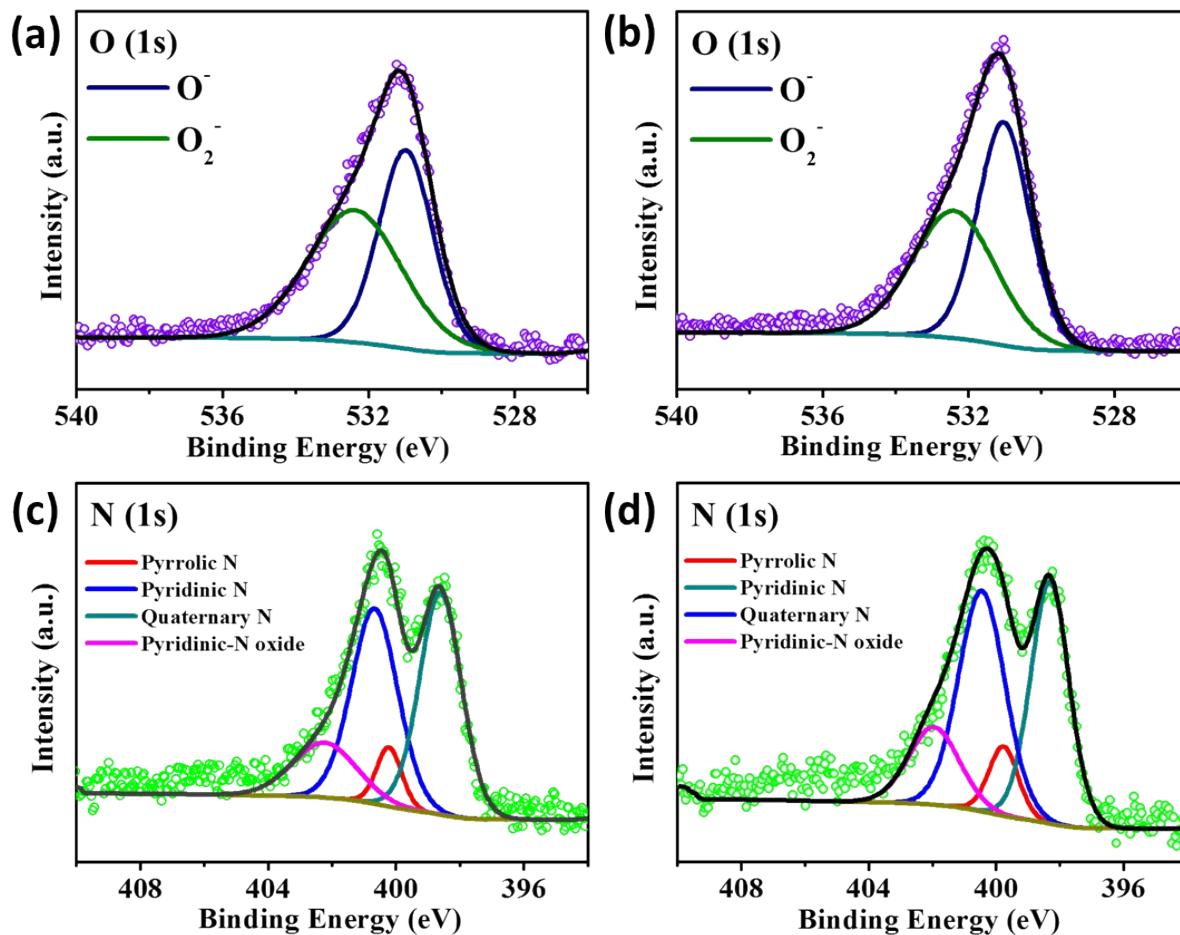


Figure S7. Ex-situ XPS analysis with $\text{WS}_2@\text{MTCNFs}$: O 1s spectra (a) before and (b) after exposure to NO_2 in dry air. N 1s spectra (c) before and (d) after exposure to NO_2 in dry air.

S8. Temperature dependency of sensing characteristics of WS₂@MTCNFs

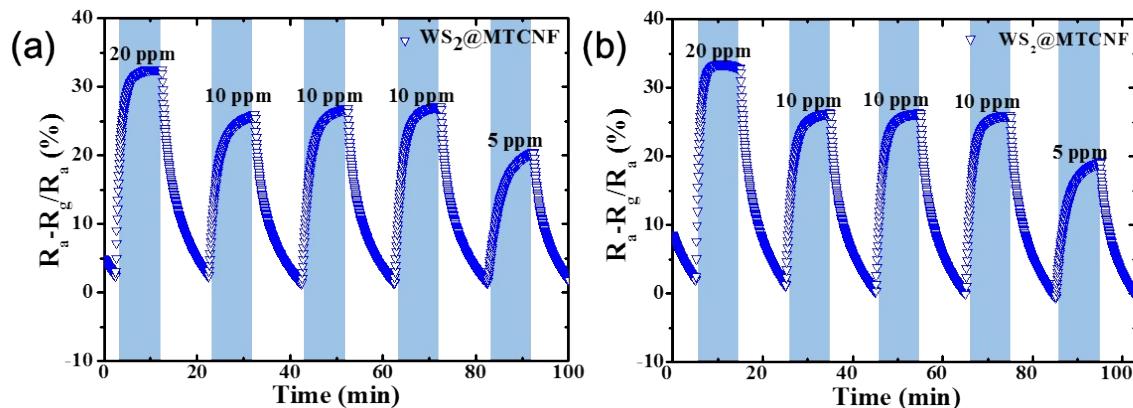


Figure S8. Dynamic response transients of WS₂@MTCNFs toward NO₂ in the concentration rage of 20-5 ppm at (a) 25 °C and (b) 80 °C.

For analysis regarding temperature dependency of the sensing materials, the sensing performance of WS₂@MTNCFs was characterized at 80 °C in the concentrations of 20, 10, and 5 ppm. As a result, any enhancement in response of the WS₂@MTNCFs was not observed, showing that the sensing material are not affected much by temperature.

S9. SEM images

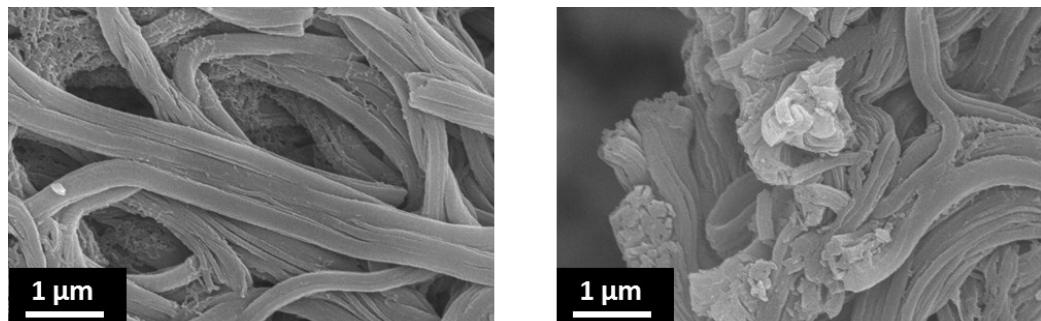


Figure S9. SEM images of CNFs obtained from combination of PAN and SAN without ATTT, followed by heat treatment. It shows that the morphology of synthesized products is much different from that of WS₂@MTCNFs.

S10. Comparison with other WS₂ gas sensors

Table S1. Recent publications on a variety of WS₂ based gas sensors.

Gas species	Materials	Working temperature	Balance gas	Measurement	Response	Exposure time	Detection limit	reference
Various gases	Multilayer WS ₂ nanoflakes	Room temp.	Dry	Source drain current	–	~25 s	–	5
Humidity	WS ₂ Nanoparticles	Room temp.	Air	Current	–	~200 s	–	6
Methanol	Metallic 1T WS ₂	Room temp.	Humid air	Impedance	–	–	–	7
H ₂	WS ₂ -Pd composite film	Room temp.	Dry N ₂	Resistance	380% at 1000 ppm	30 min	10 ppm	8
NH ₃	2nm-WS ₂ film	Room temp.	Dry N ₂	Resistance	0.2% at 60 ppm	2 min	1.2 ppm	9
NH ₃	Fluorinated 1L WS ₂	Room temp.	Dry air	PL intensity	–	2 min	–	10
NO ₂	Ag-NW@WS ₂ nanosheets	100 °C	Dry air	Current	60% at 25 ppm	5 min	–	11
NO ₂	WS ₂ @MTCNFs	Room temp.	Dry air	Resistance	15% at 1 ppm	20 min	10 ppb	This work

S11. Comparison with other TMD gas sensors for NO₂ sensing

Table S2. Recent publications on TMD based gas sensors toward NO₂ sensing.

Gas species	Materials	Working temperature	Balance gas	Measurement	Response	Exposure time	Detection limit	reference
Thin-layered MoS ₂		Room temp.	Dry N ₂	Source drain current	1372% at 1000 ppm	~300 s	–	3
Atomic-layer MoS ₂		Room temp.	Dry air	Resistance	27% at 20 ppm	2 min	–	4
CVD Atomic-layer MoS ₂		Room temp.	Dry N ₂	Resistance	150% at 1200 ppb	5 min	120 ppb	12
Graphene/MoS ₂		100 °C	Dry N ₂	Resistance	3% at 1.2 ppm	5 min	–	13
Graphene/MoS ₂		150 °C	Dry air	Resistance	3% at 5 ppm	5 min	–	14
NO ₂	MoS ₂ /SnO ₂	Room temp.	Dry air	Conductance	0.6% at 0.5 ppm	~750 s	0.5 ppm	15
Exfoliated MoS ₂ flakes		200 °C	Dry air	Resistance	1.6% at 1 ppm	120 min	20 ppb	16
Vertically aligned MoS ₂		Room temp.	Dry N ₂	Resistance	4% at 100 ppm	10 min	–	17
MoS ₂ /Graphene hybrid aerogel		200 °C	Dry N ₂	Resistance	9% at 0.5 ppm	10 min	14 ppb	18
Ag-NW@WS ₂ nanosheets		100 °C	Dry air	Current	60% at 25 ppm	5 min	–	11
WS ₂ @MTCNFs		Room temp.	Dry air	Resistance	15% at 1 ppm	20 min	10 ppb	This work

Note and References

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